

Elucidating the Role of Functional Groups of Ligands for Selective Metal Blocking via Vapor-Phase SAM Deposition

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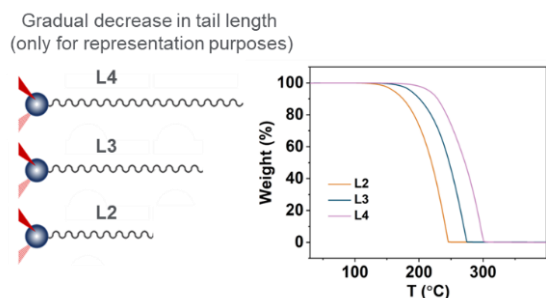


Figure 1 Reduction in $t_{1/2}$ (TGA) with gradual decrease in the tail length of L4

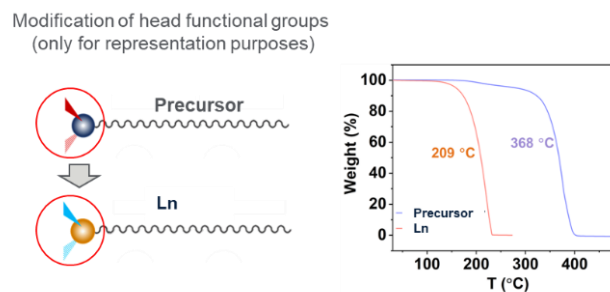


Figure 2 Volatility enhancement of L_n by modifying the head-group

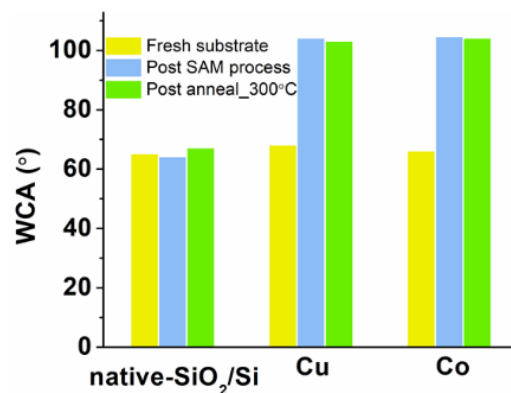


Figure 3 Water contact angle of fresh substrates, post L_n SAM growth, and after annealing the samples at 300 °C

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